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**(54) Title (EN):** EXHAUST GAS PURIFICATION CATALYST

**(54) Title (FR):** CATALYSEUR DE PURIFICATION DE GAZ D'ÉCHAPPEMENT

**(54) Title (JA):** 排ガス浄化用触媒

**(57) Abstract:**

**(EN):** The present invention provides an exhaust gas purification catalyst comprising a substrate 11 and a catalyst layer 20 provided on the substrate 11. The catalyst layer 20 includes a catalytic metal and a support material 21 supporting the catalytic metal. The support material 21 includes an OSC material 22 having oxygen storage capacity, and a carrier 23 other than the OSC material. The average particle size  $D_x$  of the OSC material 22 is at least 1.5  $\mu\text{m}$  and is greater than the average particle size  $D_y$  of the carrier 23 other than the OSC material.

**(FR):** La présente invention concerne un catalyseur de purification de gaz d'échappement comprenant un substrat 11 et une couche de catalyseur 20 disposée sur le substrat 11. La couche de catalyseur 20 comprend un métal catalytique et un matériau de support 21 supportant le métal catalytique. Le matériau de support 21 comprend un matériau OSC 22 ayant une capacité de stockage d'oxygène, et un support 23 autre que le matériau OSC. La taille moyenne de particule  $D_x$  du matériau OSC 22 est d'au moins 1,5  $\mu\text{m}$  et est supérieure à la taille moyenne de particule  $D_y$  du support 23 autre que le matériau OSC.

**(JA):** 本発明によって、基材 11 と、基材 11 の上に設けられている触媒層 20 と、を備える排ガス浄化用触媒が提供される。触媒層 20 は、触媒金属と、上記触媒金属を担持している担持材料 21 と、を含む。担持材料 21 は、酸素吸蔵能を有する OSC 材 22 と、OSC 材以外の担体 23 と、を含む。OSC 材 22 の平均粒子径  $D_x$  は、1.5  $\mu\text{m}$  以上であり、かつ、上記 OSC 材以外の担体 23 の平均粒子径  $D_y$  よりも大きい。

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